

ABSTRACT OF THE DISCLOSURE

An exposure method includes the steps of acquiring information of an alignment mark formed on an object to be exposed, by changing a value of a device parameter, the information being used for an alignment between a reticle and the object, the reticle forming a circuit pattern to be transferred to the object, and the value being able to be set in an exposure apparatus, determining the value of the device parameter of the exposure apparatus based on the information acquired in the acquiring step, and transferring the pattern onto the object using the exposure apparatus that sets the value of the device parameter, which has been determined.